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(54) Title: METHODS AND COMPOSITIONS FOR CHEMICAL MECHANICAL POLISHING SUBSTRATES COVERED WITH AT LEAST TWO DIELECTRIC MATERIALS

(57) Abstract: Methods and compositions are provided for planarizing a substrate surface with reduced or minimal defects in surface topography. In one aspect, a method is provided for processing a substrate including positioning a substrate comprising at least first dielectric material and second dielectric material disposed thereon in a polishing apparatus, polishing the substrate with a first polishing composition having a first selectivity, and polishing the substrate with a second polishing composition having a second selectivity greater than the first selectivity.

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A. CLASSII IPC 7	FICATION OF SUBJECT MATTER H01L21/3105 H01L21/768 C09G1/02	B24B37/04		
According to	International Patent Classification (IPC) or to both national classificat	tion and IPC		
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